

UNITED STATES DEPARTMENT OF COMMERCE

Patent and Trademark Office

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APPLICATION NO.	FILING DATE	FIRST NAMED	NVENTOR		ATTORNEY DOCKET NO.
09/362,192	07/28/99	YAMAZAKI		s	0756-2011
- 022204 NIXON PEABODY, LKP -		MMC2/1011	\neg	EXAMINER	
				SIMKOVIC.V	
8180 GREENS! SUITE 800	BORO DRIVE			ART UNIT	PAPER NUMBER
MCLEAN VA 22102				2812	
				DATE MAILED:	
					10/11/01

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

	Application No.	Applicant(s)					
<i>'</i>	• •						
" Office Action Summany	09/362,195	SPARTIOTIS ET AL.					
Office Action Summary	Examin r	Art Unit					
The MAILING DATE of this communication app	Viktor Simkovic ears on the cover sheet with the c	2812					
Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status							
1) Responsive to communication(s) filed on 30 J	uly 2001 .						
2a)⊠ This action is FINAL . 2b)□ Thi	s action is non-final.						
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposition of Claims							
4) Claim(s) 45-72 is/are pending in the application.							
4a) Of the above claim(s) is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>45-72</u> is/are rejected.							
7) Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction and/or election requirement.							
Application Papers							
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
11) The proposed drawing correction filed on is: a) □ approved b) □ disapproved by the Examiner. If approved, corrected drawings are required in reply to this Office action.							
12) The oath or declaration is objected to by the Examiner.							
Priority under 35 U.S.C. §§ 119 and 120							
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).							
a)⊠ All b)□ Some * c)□ None of:							
1.⊠ Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No							
3. Copies of the certified copies of the priority documents have been received in this National Stage							
application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.							
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).							
 a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121. 							
Attachment(s)							
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 4) Interview Summary (PTO-413) Paper No(s) 5) Notice of Informal Patent Application (PTO-152) 6) Other:							
J.S. Patent and Trademark Office							

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DETAILED ACTION

Claim Objections

Claim 45 is objected to because of the following informalities: The phrase "a gate insulating film formed" should read –a gate insulating film is formed--. Appropriate correction is required.

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 48 recites the limitation "gate oxide film" in line 1, and the limitation "without exposing the air". There is insufficient antecedent basis for these limitations in the claim. Thus this claim is rejected.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 45, 47, 60, 62-63, and 67-72 are rejected under 35 U.S.C. 103(a) as being unpatentable over Fonash et al. in view of Makita et al.

Fonash et al. teach a method for manufacturing a semiconductor device comprising the steps of :

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subjecting a semiconducting film to oxygen plasma, thereby forming a gate insulating film on said semiconducting film;

crystallizing said semiconducting film to obtain a crystalline semiconductor film.

See column 3, lines 11-17, and 39-53, as well as column 4, lines 40-67. Fonash et al. fail to teach, however, the step of contacting a material for promoting crystallization to at least a part of the semiconductor film formed over the substrate. Such a step is well known in the art and is taught by Makita et al. Makita et al. teach introducing a metal catalyst into the film to promote crystallization. it would have been obvious to one of ordinary skill in the art at the time of the invention to combine this step with the step of using oxygen plasma, as the use of a metal catalyst to promote crystallization is well known, and one of ordinary skill in the art would know that combining two such steps, each of which enhance crystallization, together, would further improve the overall level of crystallization. With regards to claim 47, the crystallization is done in a solid state.

With regards to claims 67-72, Makita et al. teach the use of Ni, Co, Pd, Pt, Cu, Ag, Au, In, Sn, Sb, and Al as appropriate catalysts for crystallization (See column 24, line 21)

Claims 46, 49-59, 61, 64-66 are rejected under 35 U.S.C. 103(a) as being unpatentable over Fonash et al. in view of Makita et al. as applied to claim 45 above, and further in view of Miyasaka ('516). While Fonash et al. do not teach a step of crystallizing the semiconductor film with a laser light, such a step is taught by Miyasaka et al. and it would have been obvious to one of ordinary skill in the art at the time of the invention to use a laser, as lasers are well known in the art to be an effective means for

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crystallizing silicon thin films. With regard to claim 49, Fonash et al. teach the use of helium in column 6, line 64.

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Viktor Simkovic whose telephone number is 703-308-6170. The examiner can normally be reached on Mon - Fri, 9:00 - 6:00, except every other Friday.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Niebling can be reached on 703-308-3325. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-1782.

Viktor Simkovic October 4, 2001

> John F. Niebling Supervisory Patent Examiner Technology Center 2800